



SNS COLLEGE OF ENGINEERING



DEPARTMENT OF ELECTRONICS & COMMUNICATION ENGINEERING

19EC505-VLSI DESIGN

III YEAR/₁ V SEMESTER

UNIT 1 -MOS TRANSISTOR PRINCIPLE

TOPIC 4 -MOS IV CHARACTERISTICS



OUTLINE



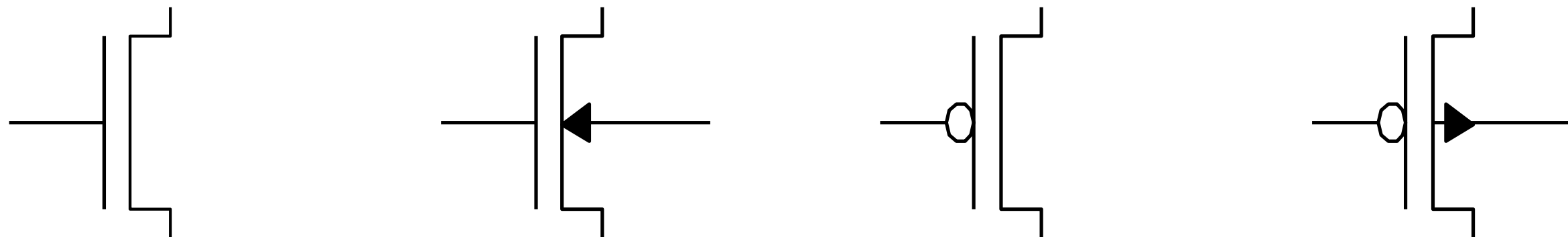
- INTRODUCTION
- MOS CAPACITOR
- TERMINAL VOLTAGES
- NMOS CUTOFF
- NMOS LINEAR
- NMOS SATURATION
- I-V CHARACTERISTICS
- CARRIER VELOCITY
- ACTIVITY
- NMOS & PMOS I-V PLOTS
- EXAMPLES
- ASSESSMENT
- SUMMARY



INTRODUCTION



- An ON transistor passes a finite amount of current
 - Depends on terminal voltages
 - Derive current-voltage (I-V) relationships
- Transistor gate, source, drain all have capacitance
 - $I = C (DV/Dt) \rightarrow Dt = (C/I) DV$
 - Capacitance and current determine speed
- Also explore what a “degraded level” really means

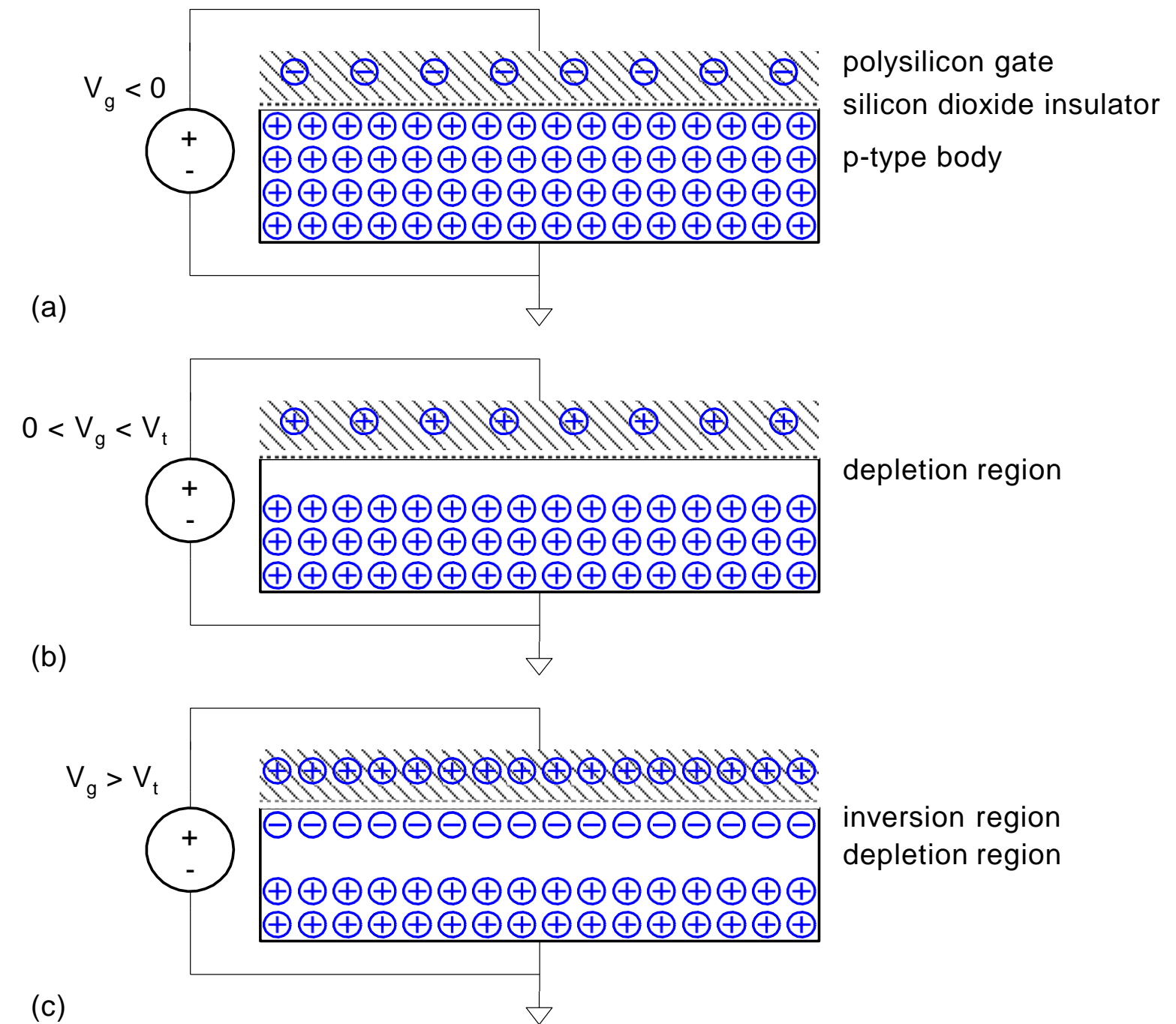




MOS CAPACITOR



- Gate and body form MOS capacitor
- Operating modes
 - Accumulation
 - Depletion
 - Inversion

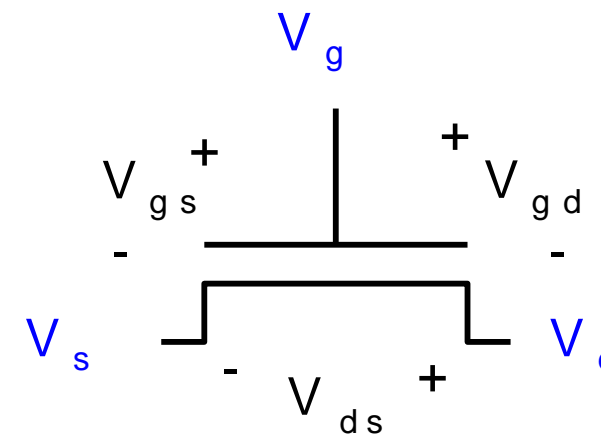




TERMINAL VOLTAGES



- Mode of operation depends on V_g , V_d , V_s
 - $V_{gs} = V_g - V_s$
 - $V_{gd} = V_g - V_d$
 - $V_{ds} = V_d - V_s = V_{gs} - V_{gd}$
- Source and drain are symmetric diffusion terminals
 - By convention, source is terminal at lower voltage, Hence $V_{ds} \geq 0$
- nMOS body is grounded. First assume source is 0 too.
- Three regions of operation
 - Cutoff
 - Linear
 - Saturation

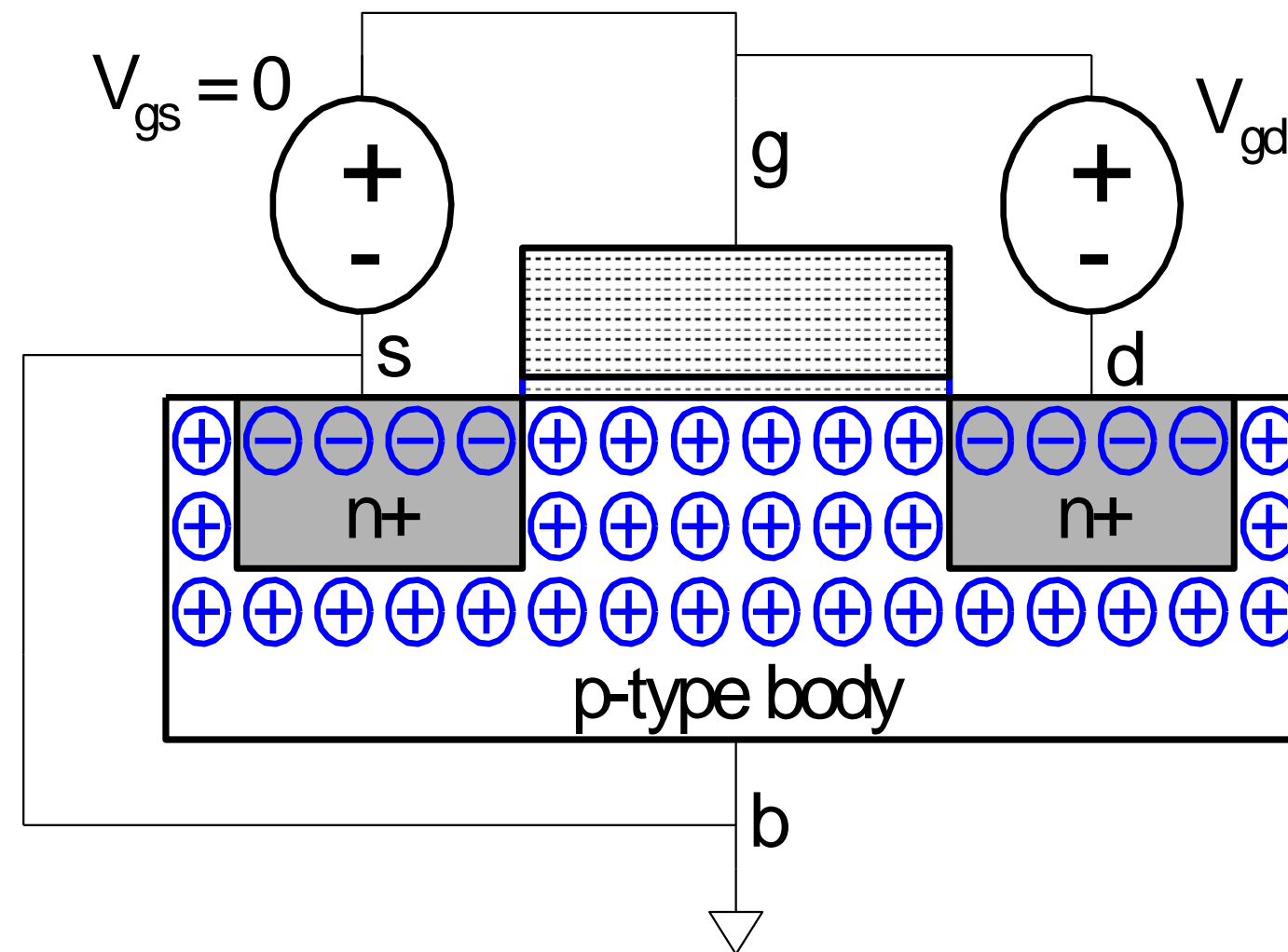




NMOS CUTOFF



- No channel
- $I_{ds} = 0$

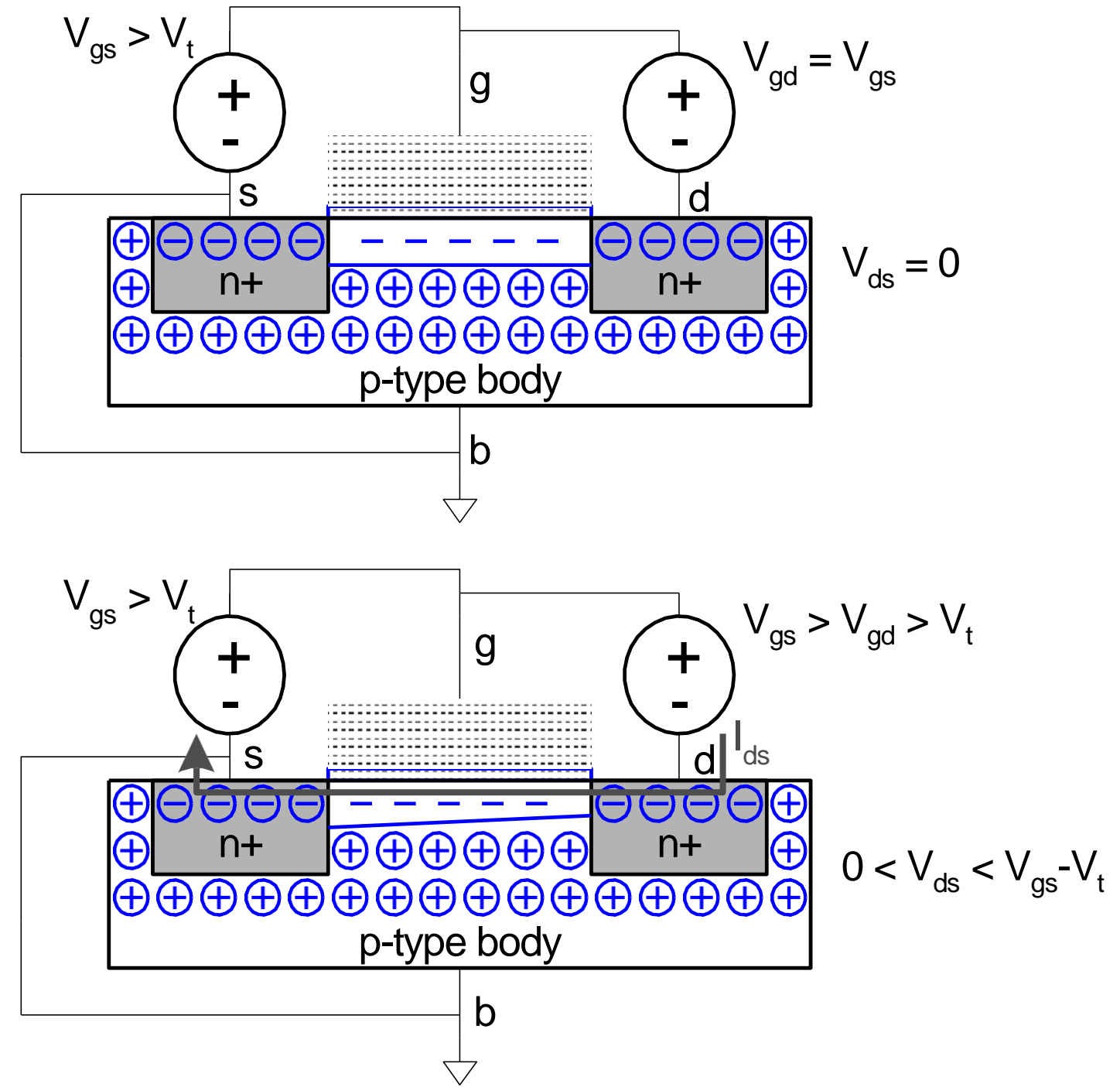




NMOS LINEAR



- Channel forms
- Current flows from d to s
–e⁻ from s to d
- I_{ds} increases with V_{ds}
- Similar to linear resistor

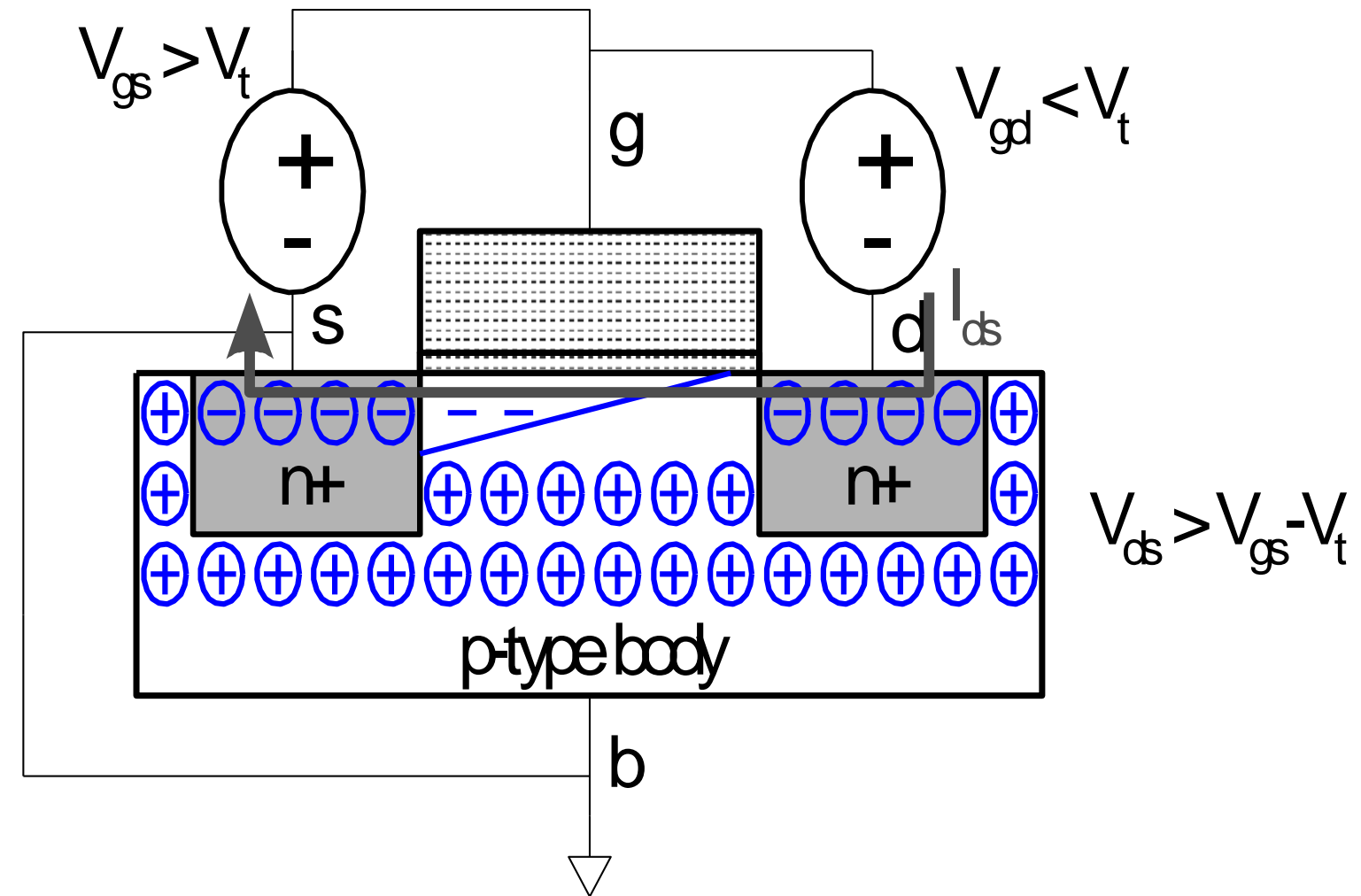




NMOS SATURATION



- Channel pinches off
- I_{ds} independent of V_{ds}
- We say current saturates
- Similar to current source





I-V CHARACTERISTICS



What is I & V?????

In Linear region, I_{ds} depends on
How much charge is in the channel?
How fast is the charge moving?



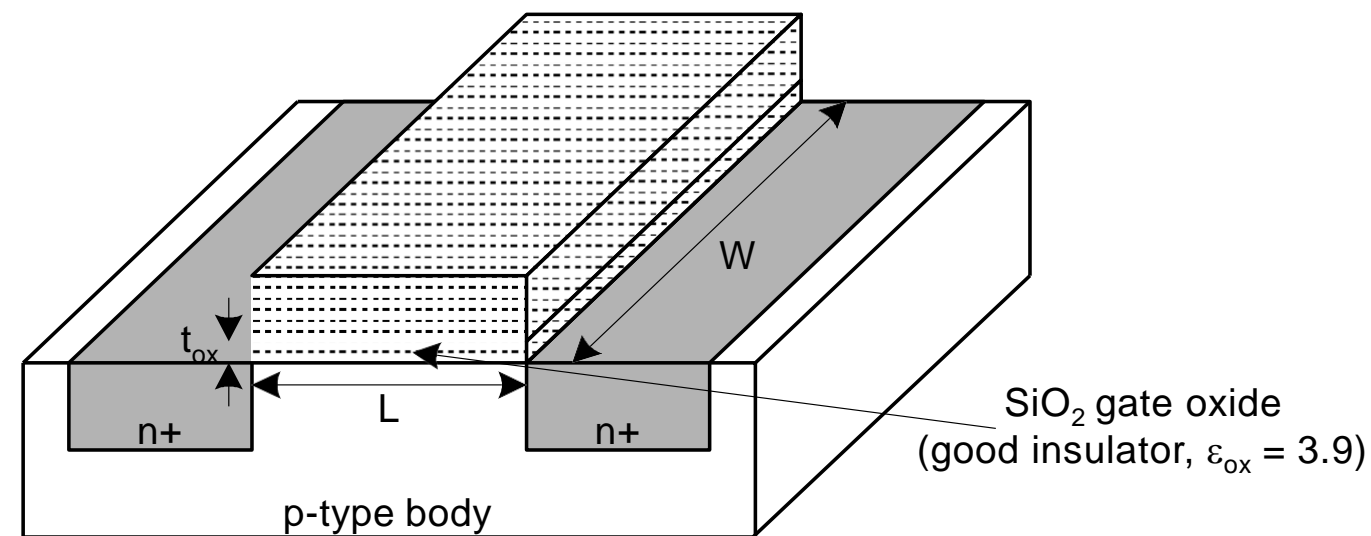
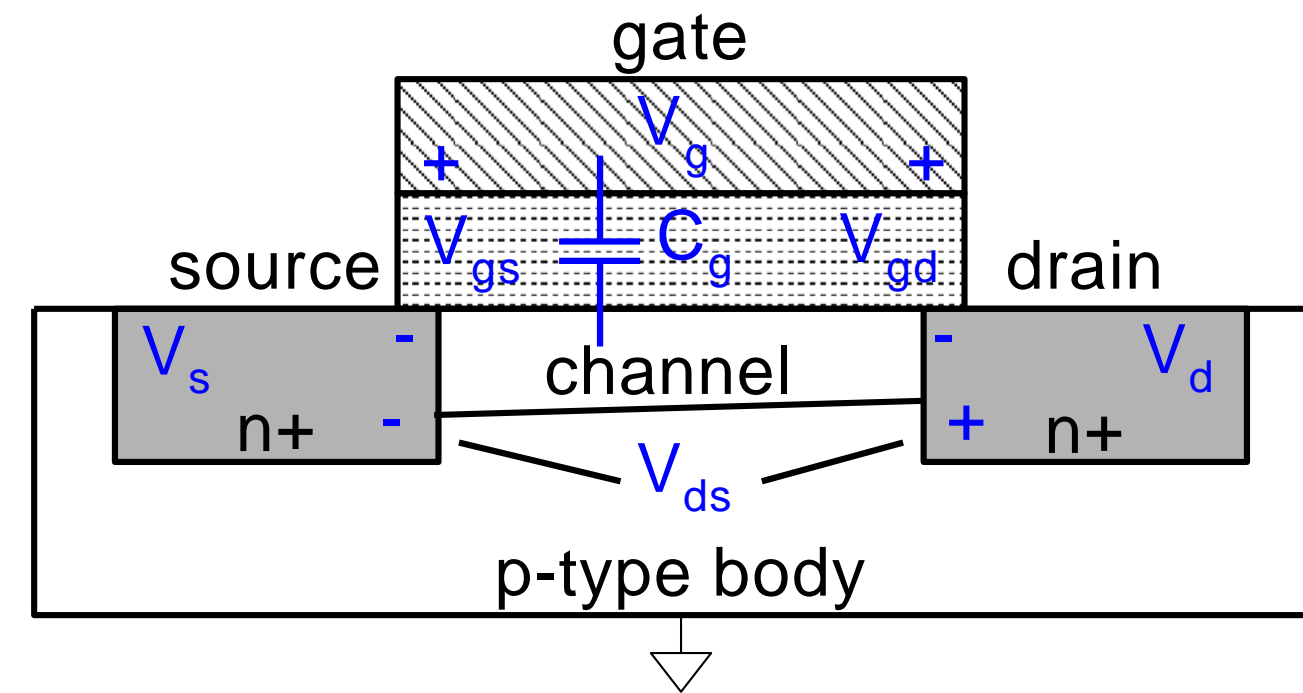
CHANNEL CHARGE



- MOS structure looks like parallel plate capacitor while operating in inversion

–Gate – oxide – channel

- $Q_{\text{channel}} = CV$
- $C = C_g = \epsilon_{\text{ox}} WL/t_{\text{ox}} = C_{\text{ox}} WL$
- $V = V_{gc} - V_t = (V_{gs} - V_{ds}/2) - V_t$



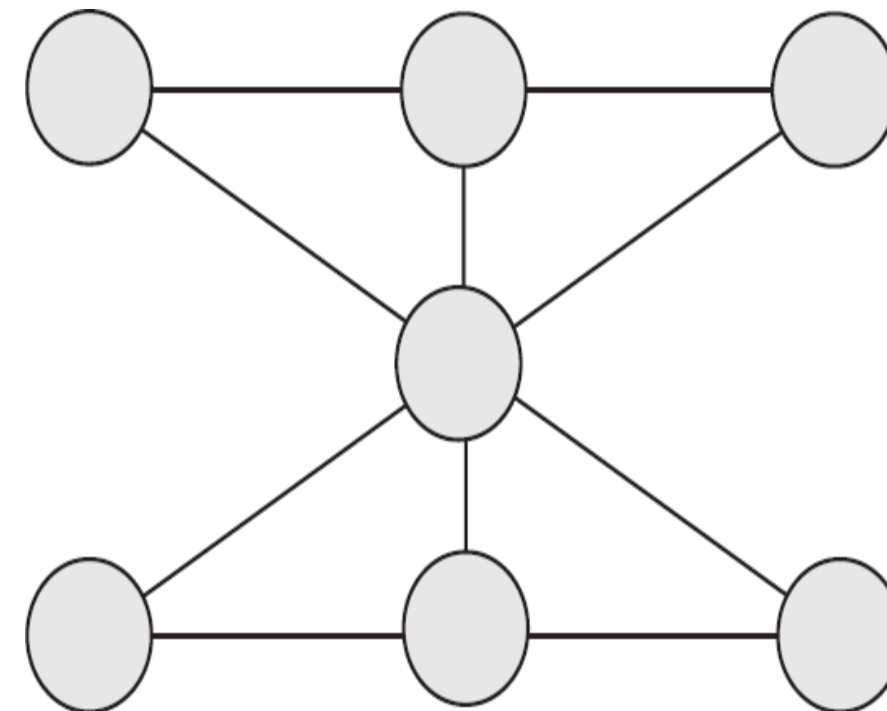


CARRIER VELOCITY & ACTIVITY



- Charge is carried by e-
- Carrier velocity v proportional to lateral E-field between source and drain
- $v = mE$ m called mobility
- $E = V_{ds}/L$
- Time for carrier to cross channel:
 $-t = L / v$

- Can you put the numbers 1 to 7 In the circles so that every line adds up to 12? You can use each number only once.





NMOS LINEAR I-V



- Now we know
 - How much charge Q_{channel} is in the channel
 - How much time t each carrier takes to cross

$$I_{ds} = \frac{Q_{\text{channel}}}{t}$$

$$= \mu C_{\text{ox}} \frac{W}{L} \left(\left| V_{gs} - V_t - \frac{V_{ds}}{2} \right| \right) V_{ds}$$

$$= \beta \left(\left| V_{gs} - V_t - \frac{V_{ds}}{2} \right| \right) V_{ds}$$

$$\beta = \mu C_{\text{ox}} \frac{W}{L}$$



NMOS SATURATION I-V

- If $V_{gd} < V_t$, channel pinches off near drain
 - When $V_{ds} > V_{dsat} = V_{gs} - V_t$
- Now drain voltage no longer increases current

PMOS I-V



- All dopings and voltages are inverted for pMOS
- Mobility m_p is determined by holes
 - Typically 2-3x lower than that of electrons m_n
 - 120 $\text{cm}^2/\text{V}^*\text{s}$ in AMI 0.6 μm process
- Thus pMOS must be wider to provide same current
 - In this class, assume $m_n / m_p = 2$



NMOS I-V SUMMARY



- Shockley 1st order transistor models

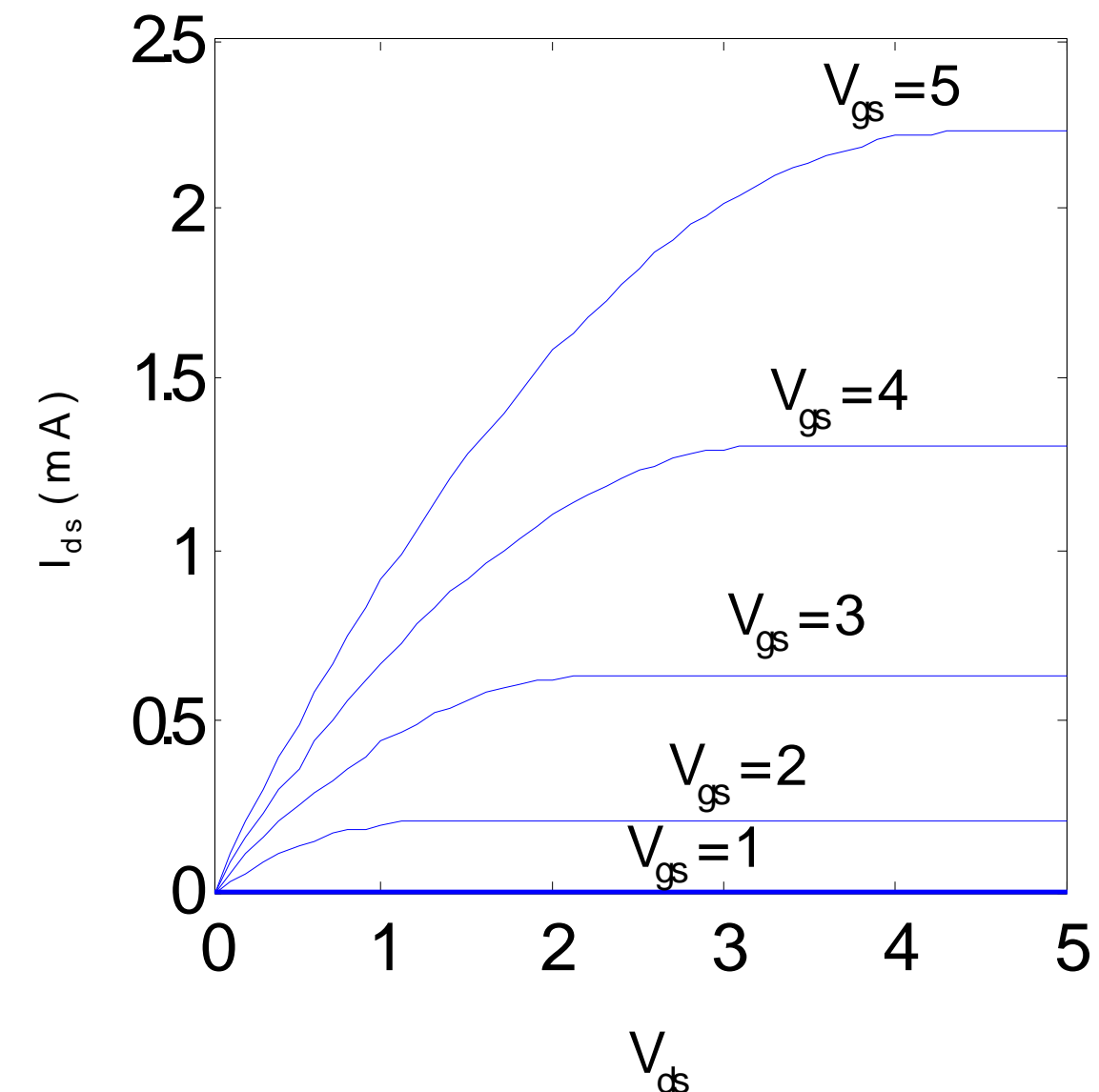
$$I_{ds} = \begin{cases} 0 & V_{gs} < V_t & \text{cutoff} \\ \beta \left(V_{gs} - V_t - \frac{V_{ds}}{2} \right) V_{ds} & V_{ds} < V_{dsat} & \text{linear} \\ \frac{\beta}{2} (V_{gs} - V_t)^2 & V_{ds} > V_{dsat} & \text{saturation} \end{cases}$$



EXAMPLE



- We will be using a 0.6 μm process for your project
 - From AMI Semiconductor
 - $t_{\text{ox}} = 100 \text{ \AA}$
 - $m = 350 \text{ cm}^2/\text{V}^*\text{s}$
 - $V_t = 0.7 \text{ V}$
- Plot I_{ds} vs. V_{ds}
 - $V_{\text{gs}} = 0, 1, 2, 3, 4, 5$
 - Use $W/L = 4/2$

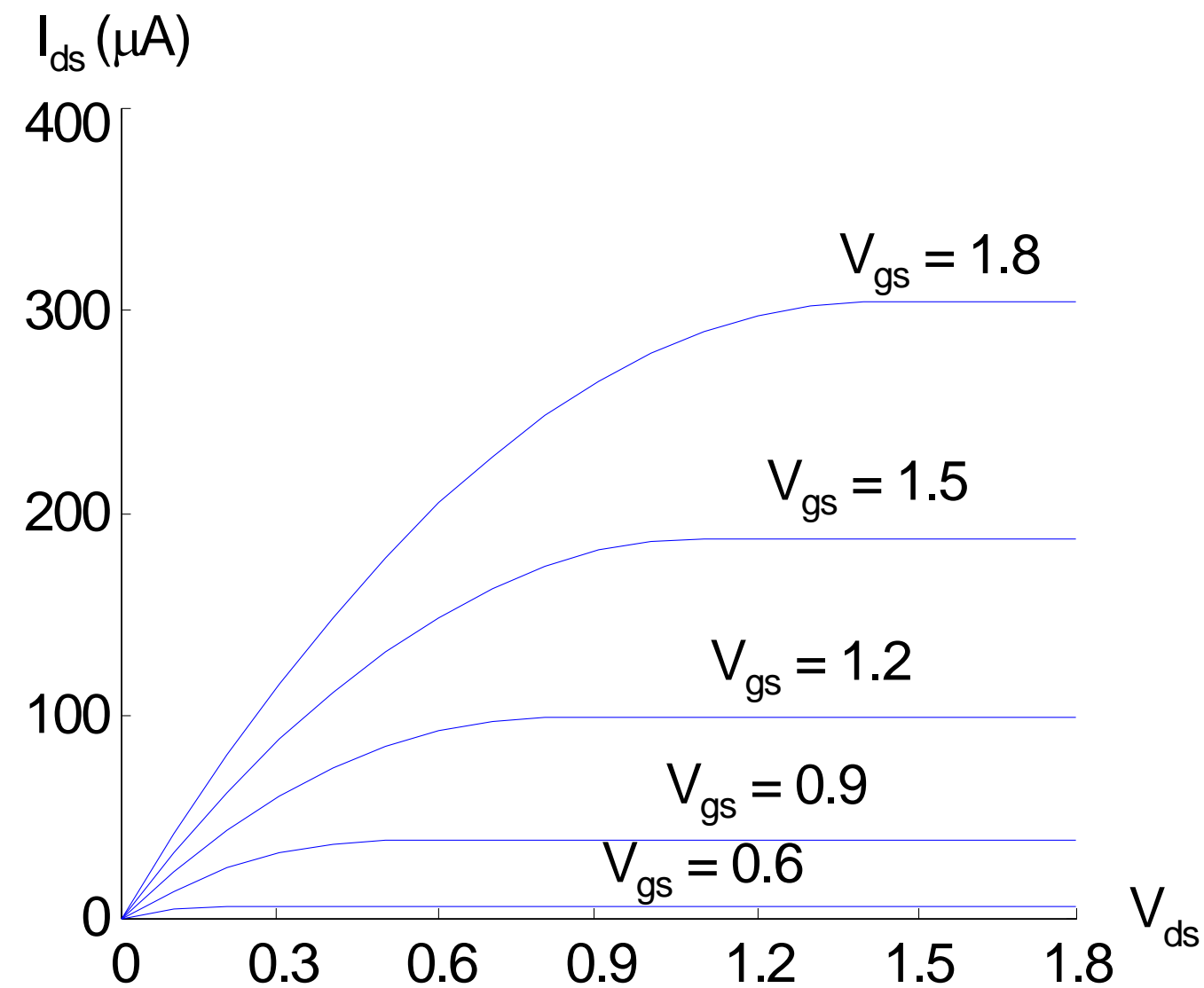




IDEAL NMOS I-V PLOT



- 180 nm TSMC process
- Ideal Models
 - $b = 155(W/L) \text{ mA/V}^2$
 - $V_t = 0.4 \text{ V}$
 - $V_{DD} = 1.8 \text{ V}$

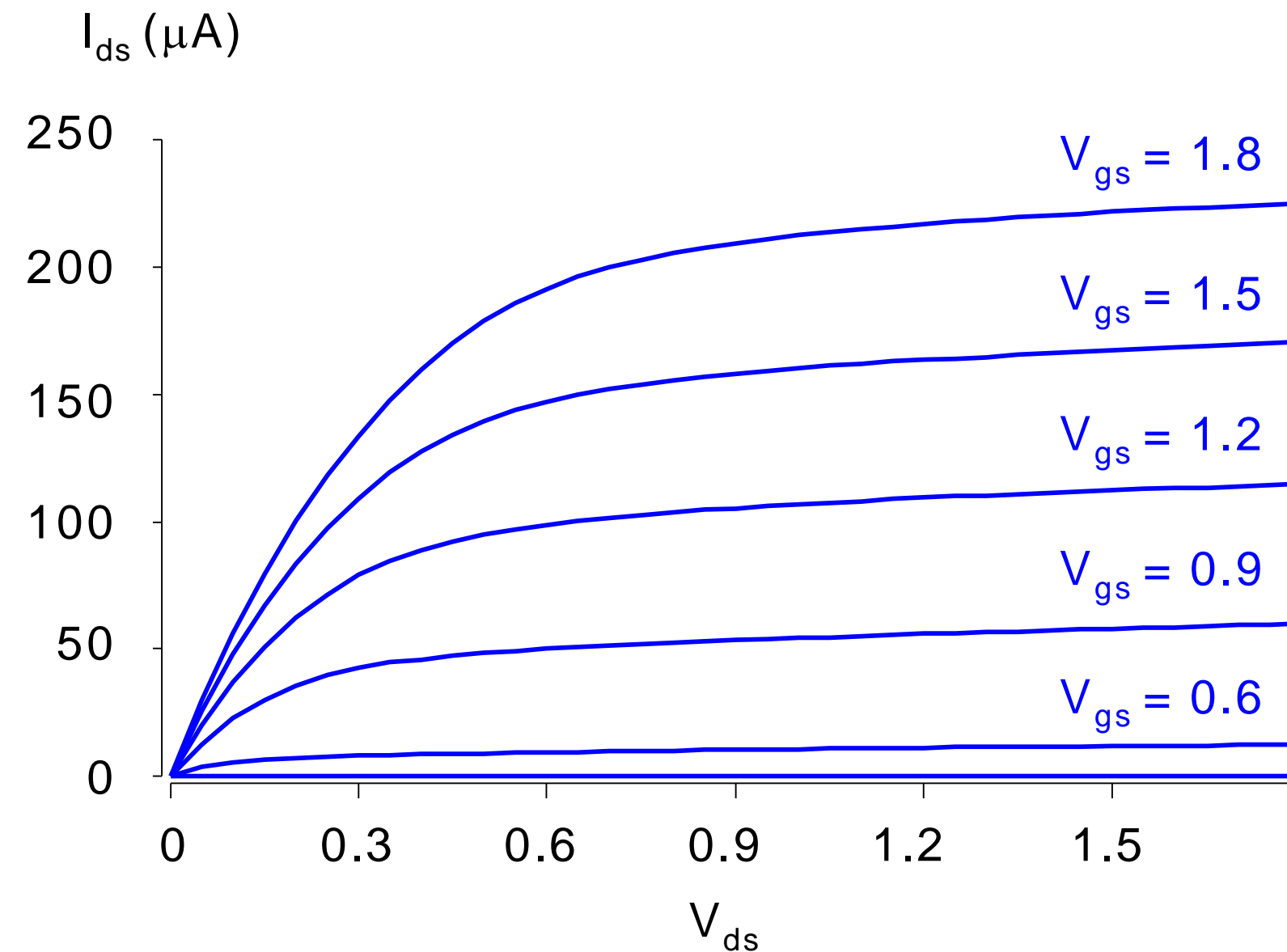




SIMULATED NMOS I-V PLOT



- 180 nm TSMC process
- BSIM 3v3 SPICE models
- What differs?
 - Less ON current
 - No square law
 - Current increases
 - in saturation





ASSESSMENT



1. Compare Accumulation, Depletion, Inversion modes
2. Write the I_{ds} equations for three modes in Shockley 1st order transistor models
3. Draw pMOS I-V plot



SUMMARY & THANK YOU